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Abstract Great interest has been shown over recent years in the development of large area polysilicon active matrix displays. Availability of a reliable process for gate oxide formation over large area has proved a major barrier, despite significant advances in similar wafer processing systems.

A system has been developed for deposition of low temperature oxides on large area (up to 14 x 14 inches) glass substrates.

The characteristics of the deposited films have been studied and the suitability of the process and equipment for large area displays will be demonstrated.